

L Number	Hits	Search Text	DB	Time stamp
1	0	\$fluoroadamantyl adj (methacrylate acrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 10:03
2	1	\$fluoro\$adamantyl adj (methacrylate acrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 10:11
9	997	fluoro\$6yl adj (methacrylate acrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:04
8	22	((("2000684888") or ("2003017415") or ("2003013039") or ("6602646") or ("6596458") or ("2002150835") or ("2001044070") or ("6579659")).PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 11:17
10	766	430/907.ccls. 430/905.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:04
11	6	(430/907.ccls. 430/905.ccls.) and (fluoro\$6yl adj (methacrylate acrylate))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:04
12	247	(\$10octafluoropentyl adj (methacrylate acrylate)) (\$10fluor\$10adamantyl adj (methacrylate acrylate)) and (resist photoresist)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:12
13	6995	cyclo\$5yl adj (methacrylate acrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:12
14	12	(fluorine fluoro fluorinated) same ((bicyclic polycyclic alicyclic) near (methacrylate acrylate))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:12
15	905	fluoroalkyl near (methacrylate acrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:12
16	7916	(((\$10octafluoropentyl adj (methacrylate acrylate)) (\$10fluor\$10adamantyl adj (methacrylate acrylate)) and (resist photoresist)) (cyclo\$5yl adj (methacrylate acrylate)) ((fluorine fluoro fluorinated) same ((bicyclic polycyclic alicyclic) near (methacrylate acrylate))) (fluoroalkyl near (methacrylate acrylate))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:12
17	72	(((\$10octafluoropentyl adj (methacrylate acrylate)) (\$10fluor\$10adamantyl adj (methacrylate acrylate)) and (resist photoresist)) (cyclo\$5yl adj (methacrylate acrylate)) ((fluorine fluoro fluorinated) same ((bicyclic polycyclic alicyclic) near (methacrylate acrylate))) (fluoroalkyl near (methacrylate acrylate))) and (430/907.ccls. 430/905.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:12
18	66	(((\$10octafluoropentyl adj (methacrylate acrylate)) (\$10fluor\$10adamantyl adj (methacrylate acrylate)) and (resist photoresist)) (cyclo\$5yl adj (methacrylate acrylate)) ((fluorine fluoro fluorinated) same ((bicyclic polycyclic alicyclic) near (methacrylate acrylate))) (fluoroalkyl near (methacrylate acrylate))) and (430/907.ccls. 430/905.ccls.) not ((430/907.ccls. 430/905.ccls.) and (fluoro\$6yl adj (methacrylate acrylate)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:24

19	0	2-fluoroadamantyl adj acrylate	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:24
20	2	2-fluoroadamantyl	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:25
21	6	\$7fluoroadamantyl	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:51
22	4	\$7fluoronorbornyl	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:52
23	4	\$10fluoronorbornyl	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:53
24	3	\$10fluoroisobornyl	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:54
25	2	\$10fluoroisobornyl not \$10fluoronorbornyl	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:54
97	0	au-13035-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 13:46
98	0	au-88013035-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 13:46
-	1	("20030008231").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 10:02
-	75	fluorin\$8 near alicyclic	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/08 10:25
-	246	\$10octafluoropentyl adj (methacrylate acrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/08 10:27
-	247	(\$10octafluoropentyl adj (methacrylate acrylate)) (\$10fluor\$10adamantyl adj (methacrylate acrylate)) and (resist photoresist)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:11
-	1	\$10fluor\$10adamantyl adj (methacrylate acrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/08 11:15
-	4397	(fluorine fluoro fluorinated) near5 (methacrylate acrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/08 16:21
-	546	((fluorine fluoro fluorinated) near5 (methacrylate acrylate)) and (resist photoresist)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/08 10:36
-	546	((fluorine fluoro fluorinated) near5 (methacrylate acrylate)) and (resist photoresist)) not (fluorin\$8 near alicyclic)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/08 14:06
-	419	adamantyl adj (methacrylate acrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/08 11:30

-	0	(fluorine fluoro fluorinated) near (adamantyl adj (methacrylate acrylate))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/08 11:16
-	6990	cyclo\$5yl adj (methacrylate acrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:12
-	0	2002363222.URPN.	USPAT	2003/09/08 13:35
-	1	2001JP-0170197.prai.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/08 14:05
-	904	fluoroalkyl near (methacrylate acrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:12
-	868	(fluoroalkyl near (methacrylate acrylate)) not (((fluorine fluoro fluorinated) near5 (methacrylate acrylate)) and (resist photoresist)) not (fluorin\$8 near alicyclic))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/08 14:06
-	5854256	s ((fluoroalkyl near (methacrylate acrylate)) not (((fluorine fluoro fluorinated) near5 (methacrylate acrylate)) and (resist photoresist)) not (fluorin\$8 near alicyclic))) and (430/\$.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/08 14:07
-	58	((fluoroalkyl near (methacrylate acrylate)) not (((fluorine fluoro fluorinated) near5 (methacrylate acrylate)) and (resist photoresist)) not (fluorin\$8 near alicyclic))) and (430/\$.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/08 14:08
-	12	fluorocycloalkyl near (methacrylate acrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/08 14:19
-	44	\$fluorocyclo\$6yl adj (methacrylate acrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/08 15:27
-	44	(\$fluorocyclo\$6yl adj (methacrylate acrylate)) not (fluorocycloalkyl near (methacrylate acrylate))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/08 16:20
-	302	alicyclic near (methacrylate acrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/08 16:20
-	366	(bicyclic polycyclic alicyclic) near (methacrylate acrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/08 16:20
-	12	(fluorine fluoro fluorinated) same ((bicyclic polycyclic alicyclic) near (methacrylate acrylate))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/09 12:12
-	17	(\$10fluorine \$10fluoro \$10fluorinated nonafluoro) same ((bicyclic polycyclic alicyclic) near (methacrylate acrylate))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/09/08 16:25

ENTER SCREEN EXPRESSION OR (END):end

=>

Uploading C:\Program Files\Stnexp\Queries\10084828.str

L1 STRUCTURE UPLOADED

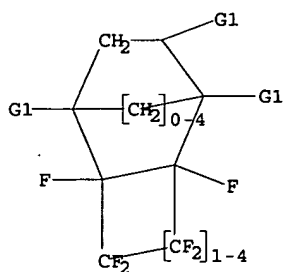
=> que L1

L2 QUE L1

=> d

L2 HAS NO ANSWERS

L1 STR



G1 H, F, Ak, CF3

STN-search
Do Not Remove

Structure attributes must be viewed using STN Express query preparation.

L2 QUE ABB=ON PLU=ON L1

=> s l2 sss sam

SAMPLE SEARCH INITIATED 13:53:36 FILE 'REGISTRY'

SAMPLE SCREEN SEARCH COMPLETED - 233 TO ITERATE

100.0% PROCESSED 233 ITERATIONS

SEARCH TIME: 00.00.01

0 ANSWERS

FULL FILE PROJECTIONS: ONLINE **COMPLETE**

BATCH **COMPLETE**

PROJECTED ITERATIONS: 3745 TO 5575

PROJECTED ANSWERS: 0 TO 0

L3 0 SEA SSS SAM L1

=>Testing the current file.... screen

ENTER SCREEN EXPRESSION OR (END):end

=> screen 970 AND 2067

L4 SCREEN CREATED

=>

Uploading C:\Program Files\Stnexp\Queries\10084828-2.str

L5 STRUCTURE UPLOADED

=> que L5 AND L4

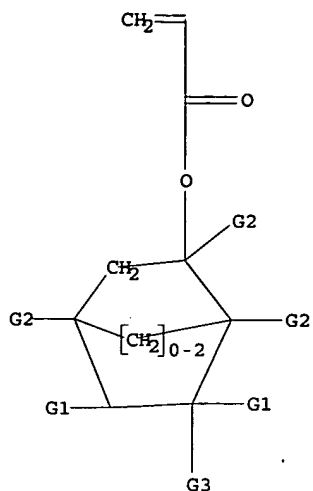
L6 QUE L5 AND L4

=> d

L6 HAS NO ANSWERS

L4 SCR 970 AND 2067

L5 STR



G1 H, F
G2 H, F, CF3, Ak
G3 F, CF2, CF3

Structure attributes must be viewed using STN Express query preparation.
L6 QUE ABB=ON PLU=ON L5 AND L4

=> s l6 sss sam
SAMPLE SEARCH INITIATED 13:54:27 FILE 'REGISTRY'
SAMPLE SCREEN SEARCH COMPLETED - 28 TO ITERATE

100.0% PROCESSED 28 ITERATIONS 0 ANSWERS
SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE **COMPLETE**
BATCH **COMPLETE**
PROJECTED ITERATIONS: 243 TO 877
PROJECTED ANSWERS: 0 TO 0

L7 0 SEA SSS SAM L5 AND L4

=>Testing the current file.... screen

ENTER SCREEN EXPRESSION OR (END):end

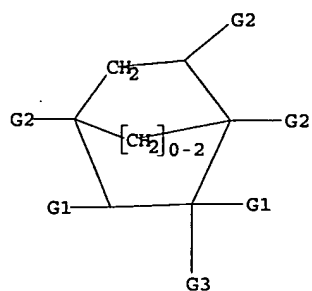
=>
Uploading C:\Program Files\Stnexp\Queries\10084828-3.str

L8 STRUCTURE UPLOADED

=> que L8

L9 QUE L8

=> d
L9 HAS NO ANSWERS
L8 STR



G1 H,F
G2 H,F,CF3,Ak
G3 F,CF2,CF3

Structure attributes must be viewed using STN Express query preparation.
L9 QUE ABB=ON PLU=ON L8

=> s l9 sss sam
SAMPLE SEARCH INITIATED 13:55:02 FILE 'REGISTRY'
SAMPLE SCREEN SEARCH COMPLETED - 14330 TO ITERATE

7.0% PROCESSED 1000 ITERATIONS 1 ANSWERS
INCOMPLETE SEARCH (SYSTEM LIMIT EXCEEDED)
SEARCH TIME: 00.00.01

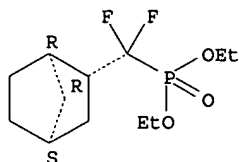
FULL FILE PROJECTIONS: ONLINE **COMPLETE**
BATCH **COMPLETE**
PROJECTED ITERATIONS: 279436 TO 293764
PROJECTED ANSWERS: 59 TO 513

L10 1 SEA SSS SAM L8

=> d

L10 ANSWER 1 OF 1 REGISTRY COPYRIGHT 2003 ACS on STN
RN 195258-93-6 REGISTRY
CN Phosphonic acid, (bicyclo[2.2.1]hept-2-ylidifluoromethyl)-, diethyl ester,
exo- (9CI) (CA INDEX NAME)
FS STEREOSEARCH
MF C12 H21 F2 O3 P
SR CA
LC STN Files: CA, CAPLUS

Relative stereochemistry.



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

1 REFERENCES IN FILE CA (1937 TO DATE)
1 REFERENCES IN FILE CAPLUS (1937 TO DATE)

=> FIL HCAPLUS, CAPLUS, USPATFULL

COST IN U.S. DOLLARS

SINCE FILE

ENTRY

TOTAL

SESSION

FULL ESTIMATED COST

3.28

3.49

FILE 'HCAPLUS' ENTERED AT 13:55:28 ON 08 SEP 2003
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.
PLEASE SEE "HELP USAGETERMS" FOR DETAILS.
COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'CAPLUS' ENTERED AT 13:55:28 ON 08 SEP 2003
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.

PLEASE SEE "HELP USAGETERMS" FOR DETAILS.
COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'USPATFULL' ENTERED AT 13:55:28 ON 08 SEP 2003
CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

=> d his

(FILE 'HOME' ENTERED AT 13:52:58 ON 08 SEP 2003)

FILE 'REGISTRY' ENTERED AT 13:53:06 ON 08 SEP 2003

L1 STRUCTURE UPLOADED
L2 QUE L1
L3 0 S L2 SSS SAM
L4 SCREEN 970 AND 2067
L5 STRUCTURE UPLOADED
L6 QUE L5 AND L4
L7 0 S L6 SSS SAM
L8 STRUCTURE UPLOADED
L9 QUE L8
L10 1 S L9 SSS SAM

FILE 'HCAPLUS, CAPLUS, USPATFULL' ENTERED AT 13:55:28 ON 08 SEP 2003

=> s l3 or l7 or l10

L11 2 L3 OR L7 OR L10

=> d l11 1-2 ibib hitstr

L11 ANSWER 1 OF 2 HCAPLUS COPYRIGHT 2003 ACS on STN

ACCESSION NUMBER: 1997:566255 HCAPLUS

DOCUMENT NUMBER: 127:234358

TITLE: Conjugate addition reactions of a
(diethoxyphosphinoyl)difluoromethyl anion equivalent
to acyclic and cyclic vinyl sulfones

AUTHOR(S): Blades, K.; Lapotre, D.; Percy, J. M.

CORPORATE SOURCE: Sch. Chemistry, Univ. Birmingham, Edgbaston,
Birmingham, B15 2TT, UK

SOURCE: Tetrahedron Letters (1997), 38(33), 5895-5898

CODEN: TELEAY; ISSN: 0040-4039

PUBLISHER: Elsevier

DOCUMENT TYPE: Journal

LANGUAGE: English

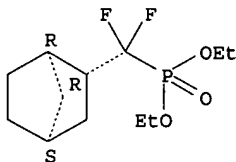
IT 195258-93-6P

RL: SPN (Synthetic preparation); PREP (Preparation)
(prepn. of)

RN 195258-93-6 HCAPLUS

CN Phosphonic acid, (bicyclo[2.2.1]hept-2-yl)difluoromethyl-, diethyl ester,
exo- (9CI) (CA INDEX NAME)

Relative stereochemistry.



L11 ANSWER 2 OF 2 CAPLUS COPYRIGHT 2003 ACS on STN

ACCESSION NUMBER: 1997:566255 CAPLUS

DOCUMENT NUMBER: 127:234358

TITLE: Conjugate addition reactions of a
(diethoxyphosphinoyl)difluoromethyl anion equivalent
to acyclic and cyclic vinyl sulfones

AUTHOR(S): Blades, K.; Lapotre, D.; Percy, J. M.

CORPORATE SOURCE: Sch. Chemistry, Univ. Birmingham, Edgbaston,
Birmingham, B15 2TT, UK

SOURCE: Tetrahedron Letters (1997), 38(33), 5895-5898

CODEN: TELEAY; ISSN: 0040-4039

PUBLISHER: Elsevier

DOCUMENT TYPE: Journal

LANGUAGE: English

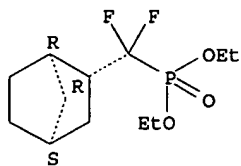
IT 195258-93-6P

RL: SPN (Synthetic preparation); PREP (Preparation)
(prepn. of)

RN 195258-93-6 CAPLUS

CN Phosphonic acid, (bicyclo[2.2.1]hept-2-yl)difluoromethyl-, diethyl ester,
exo- (9CI) (CA INDEX NAME)

Relative stereochemistry.



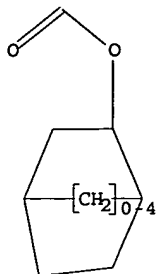
=> que L4

L5 QUE L4

=> d

L5 HAS NO ANSWERS

L4 STR



Structure attributes must be viewed using STN Express query preparation.
L5 QUE ABB=ON PLU=ON L4

=> s 15 sss sam

SAMPLE SEARCH INITIATED 14:03:26 FILE 'REGISTRY'

SAMPLE SCREEN SEARCH COMPLETED - 17471 TO ITERATE

5.7% PROCESSED 1000 ITERATIONS

27 ANSWERS

INCOMPLETE SEARCH (SYSTEM LIMIT EXCEEDED)

SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE **COMPLETE**
BATCH **COMPLETE**

PROJECTED ITERATIONS: 341515 TO 357325

PROJECTED ANSWERS: 8131 TO 10737

L6 27 SEA SSS SAM L4

=> d

L6 ANSWER 1 OF 27 REGISTRY COPYRIGHT 2003 ACS on STN

RN 565462-43-3 REGISTRY

CN Bicyclo[2.2.1]heptane-2-carboxylic acid, 2-(benzoylamino)-3-
[(ethoxycarbonyl)oxy]-, ethyl ester, (1R,2R,3S,4S)-rel- (9CI) (CA INDEX
NAME)

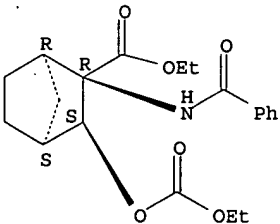
FS STEREOSEARCH

MF C20 H25 N O6

SR CA

LC STN Files: CA, CAPLUS

Relative stereochemistry.



PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

1 REFERENCES IN FILE CA (1937 TO DATE)

1 REFERENCES IN FILE CAPLUS (1937 TO DATE)

=> FIL HCAPLUS, CAPLUS, USPATFULL

COST IN U.S. DOLLARS

SINCE FILE

ENTRY

TOTAL

SESSION

FULL ESTIMATED COST

4.96

5.17

FILE 'HCAPLUS' ENTERED AT 14:03:59 ON 08 SEP 2003
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.
PLEASE SEE "HELP USAGETERMS" FOR DETAILS.
COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'CAPLUS' ENTERED AT 14:03:59 ON 08 SEP 2003
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.
PLEASE SEE "HELP USAGETERMS" FOR DETAILS.
COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'USPATFULL' ENTERED AT 14:03:59 ON 08 SEP 2003
CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

=> s 16
L7 139 L6

=> s 17 and (photoresist or resist)
L8 26 L7 AND (PHOTORESIST OR RESIST)

=> s 18 and (fluor?)
L9 7 L8 AND (FLUOR?)

=> duplicates remove 19
DUPLICATE PREFERENCE IS 'HCAPLUS, CAPLUS, USPATFULL'
KEEP DUPLICATES FROM MORE THAN ONE FILE? Y/(N):n
PROCESSING COMPLETED FOR L9
L10 6 DUPLICATE REMOVE L9 (1 DUPLICATE REMOVED)

=> d l10 1-6 ibib hitstr

L10 ANSWER 1 OF 6 USPATFULL on STN
ACCESSION NUMBER: 2003:126971 USPATFULL
TITLE: Polymer, resist composition and patterning
process
INVENTOR(S): Nishi, Tsunehiro, Niigata-ken, JAPAN
Hasegawa, Koji, Niigata-ken, JAPAN
Kinsho, Takeshi, Niigata-ken, JAPAN

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 2003087183	A1	20030508
APPLICATION INFO.:	US 2002-230341	A1	20020829 (10)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 2001-262833	20010831
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	APPLICATION	
LEGAL REPRESENTATIVE:	BIRCH STEWART KOLASCH & BIRCH, PO BOX 747, FALLS CHURCH, VA, 22040-0747	
NUMBER OF CLAIMS:	4	
EXEMPLARY CLAIM:	1	
LINE COUNT:	1550	
CAS INDEXING IS AVAILABLE FOR THIS PATENT.		
IT 521950-67-4P		

(polymer and resist compn. for deep-UV and electron beam patterning
process)

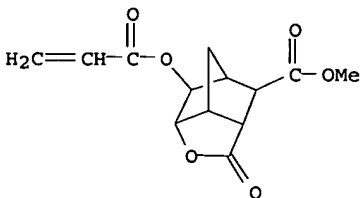
RN 521950-67-4 USPATFULL

CN 3,5-Methano-2H-cyclopenta[b]furan-7-carboxylic acid, hexahydro-2-oxo-6-[(1-oxo-2-propenyl)oxy]-, methyl ester, polymer with 2,5-furandione, 2-methyltricyclo[3.3.1.1^{3,7}]dec-2-yl 2-propenoate and spiro[bicyclo[2.2.1]hept-5-ene-2,3'-(2'H)-furan]-5'-(4'H)-one (9CI) (CA INDEX NAME)

CM 1

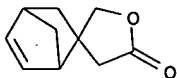
CRN 449759-66-4

CMF C13 H14 O6



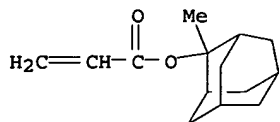
CM 2

CRN 282542-79-4
CMF C10 H12 O2



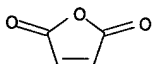
CM 3

CRN 249562-06-9
CMF C14 H20 O2



CM 4

CRN 108-31-6
CMF C4 H2 O3



L10 ANSWER 2 OF 6 USPATFULL on STN

ACCESSION NUMBER: 2003:10538 USPATFULL

TITLE: Novel (meth) acrylates having lactone structure, polymers, photoresist compositions and patterning process

INVENTOR(S): Kinsho, Takeshi, Niigata-ken, JAPAN
Hasegawa, Koji, Niigata-ken, JAPAN

PATENT ASSIGNEE(S): Watanabe, Takeru, Niigata-ken, JAPAN
Shin-Etsu Chemical Co., Ltd., Tokyo, JAPAN (non-U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 2003008232	A1	20030109
APPLICATION INFO.:	US 2002-167444	A1	20020613 (10)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 2001-179614	20010614
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	APPLICATION	
LEGAL REPRESENTATIVE:	MILLEN, WHITE, ZELANO & BRANIGAN, P.C., 2200 CLARENDON BLVD., SUITE 1400, ARLINGTON, VA, 22201	

NUMBER OF CLAIMS: 8
EXEMPLARY CLAIM: 1
LINE COUNT: 729

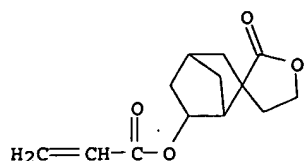
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

IT 479072-45-2P

(lactone-contg. acrylate-based excimer laser-sensitive chem. amplified pos. photoresists with good transparency)

RN 479072-45-2 USPATFULL

CN 2-Propenoic acid, dihydro-2'-oxospiro[bicyclo[2.2.1]heptane-2,3'-(2'H)-furan]-6-yl ester (9CI) (CA INDEX NAME)



L10 ANSWER 3 OF 6 HCAPLUS COPYRIGHT 2003 ACS on STN DUPLICATE 1
 ACCESSION NUMBER: 2002:868986 HCAPLUS
 DOCUMENT NUMBER: 137:370796
 TITLE: Radiation-sensitive polysiloxane resin composition
 INVENTOR(S): Iwasawa, Haruo; Hayashi, Akihiro; Shimokawa, Tsutomu;
 Yamamoto, Masafumi
 PATENT ASSIGNEE(S): JSR Co., Ltd., Japan
 SOURCE: PCT Int. Appl., 155 pp.
 CODEN: PIXXD2
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2002090423	A1	20021114	WO 2002-JP4333	20020430
W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, KE, KG, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, OM, PH, PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VN, YU, ZA, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM RW: GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG JP 2003020335 A2 20030124 JP 2002-48643 20020225 PRIORITY APPLN. INFO.: JP 2001-133795 A 20010501 JP 2002-48643 A 20020225				

OTHER SOURCE(S): MARPAT 137:370796

IT 474559-57-4P

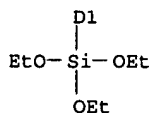
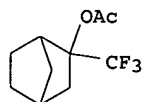
RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP
 (Properties); PREP (Preparation); USES (Uses)
 (radiation-sensitive polysiloxane resin compn.)

RN 474559-57-4 HCAPLUS

CN Bicyclo[2.2.1]heptane-2-carboxylic acid, 5(or 6)-(triethoxysilyl)-2-
 (trifluoromethyl)-, 1,1-dimethylethyl ester, polymer with 5(or
 6)-(triethoxysilyl)-.alpha.,.alpha.-bis(trifluoromethyl)bicyclo[2.2.1]hept
 ane-2-ethanol and 5(or 6)-(triethoxysilyl)-2-(trifluoromethyl)bicyclo[2.2.
 1]hept-2-yl acetate (9CI) (CA INDEX NAME)

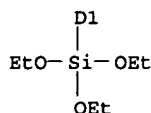
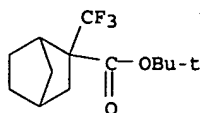
CM 1

CRN 474559-08-5
 CMF C16 H27 F3 O5 Si
 CCI IDS



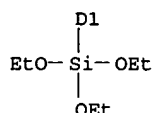
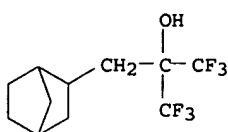
CM 2

CRN 474559-06-3
 CMF C19 H33 F3 O5 Si
 CCI IDS



CM 3

CRN 365546-74-3
CMF C17 H28 F6 O4 Si
CCI IDS



REFERENCE COUNT: 25 THERE ARE 25 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L10 ANSWER 4 OF 6 USPATFULL on STN

ACCESSION NUMBER: 2002:119480 USPATFULL

TITLE: Polymer, resist composition and patterning process

INVENTOR(S): Nishi, Tsunehiro, Nakakubiki-gun, JAPAN
Nakashima, Mutsuo, Nakakubiki-gun, JAPAN
Tachibana, Seiichiro, Nakakubiki-gun, JAPAN
Kinsho, Takeshi, Nakakubiki-gun, JAPAN
Hasegawa, Koji, Nakakubiki-gun, JAPAN
Watanabe, Takeru, Nakakubiki-gun, JAPAN
Hatakeyama, Jun, Nakakubiki-gun, JAPAN

PATENT ASSIGNEE(S): Shin-Etsu Chemical Co., Ltd., Tokyo, JAPAN (non-U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 2002061463	A1	20020523
APPLICATION INFO.:	US 2001-951523	A1	20010914 (9)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 2000-279164	20000914
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	APPLICATION	
LEGAL REPRESENTATIVE:	MILLEN, WHITE, ZELANO & BRANIGAN, P.C., 2200 CLARENDON BLVD., SUITE 1400, ARLINGTON, VA, 22201	
NUMBER OF CLAIMS:	7	
EXEMPLARY CLAIM:	1	
LINE COUNT:	1766	
CAS INDEXING IS AVAILABLE FOR THIS PATENT.		
IT 409093-65-8P		

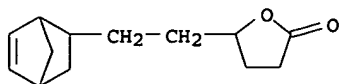
(polymers with cyclopentane rings in or adjacent to the chains for resists patternable by UV or electron beams)

RN 409093-65-8 USPATFULL

CN 2-Propenoic acid, 2-methyl-, 2-ethylbicyclo[2.2.1]hept-2-yl ester, polymer with 5-(2-bicyclo[2.2.1]hept-5-en-2-ylethyl)dihydro-2(3H)-furanone and 2,5-furandione (9CI) (CA INDEX NAME)

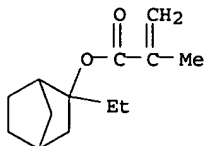
CM 1

CRN 370089-03-5
CMF C13 H18 O2



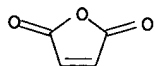
CM 2

CRN 330595-98-7
CMF C13 H20 O2



CM 3

CRN 108-31-6
CMF C4 H2 O3



L10 ANSWER 5 OF 6 USPATFULL on STN

ACCESSION NUMBER: 2001:147641 USPATFULL

TITLE: Ester compounds, polymers, resist compositions and patterning process

INVENTOR(S): Kinsho, Takeshi, Nakakubiki-gun, Japan
Nishi, Tsunehiro, Nakakubiki-gun, Japan
Kurihara, Hideshi, Usui-gun, Japan
Nakashima, Mutsuo, Nakakubiki-gun, Japan
Hasegawa, Koji, Nakakubiki-gun, Japan
Watanabe, Takeru, Nakakubiki-gun, Japan

PATENT ASSIGNEE(S): Shin-Etsu Chemical Co., Ltd., Tokyo, Japan (non-U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 6284429	B1	20010904
APPLICATION INFO.:	US 2000-512108		20000224 (9)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 1999-47406	19990225
	JP 1999-174945	19990622

DOCUMENT TYPE: Utility

FILE SEGMENT: GRANTED

PRIMARY EXAMINER: Ashton, Rosemary E.

LEGAL REPRESENTATIVE: Millen, White, Zelano & Branigan, P.C

NUMBER OF CLAIMS: 19

EXEMPLARY CLAIM: 1

LINE COUNT: 2016

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

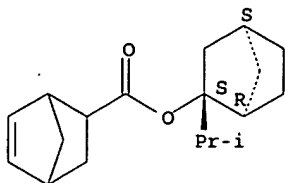
IT 290808-37-6P

(novel ester compds., polymers, resist compns. and patterning process)

RN 290808-37-6 USPATFULL

CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, (1R,2S,4S)-2-(1-methylethyl)bicyclo[2.2.1]hept-2-yl ester, rel- (9CI) (CA INDEX NAME)

Relative stereochemistry.



L10 ANSWER 6 OF 6 USPATFULL on STN

ACCESSION NUMBER: 2001:142042 USPATFULL
 TITLE: Lactone-containing compounds, polymers, resist compositions, and patterning method
 INVENTOR(S): Hasegawa, Koji, Nakakubiki-gun, Japan
 Nishi, Tsunehiro, Nakakubiki-gun, Japan
 Kinsho, Takeshi, Nakakubiki-gun, Japan
 Hatakeyama, Jun, Nakakubiki-gun, Japan
 Watanabe, Osamu, Nakakubiki-gun, Japan
 PATENT ASSIGNEE(S): Shin-Etsu Chemical Co., Ltd., Tokyo, Japan (non-U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 6280898	B1	20010828
APPLICATION INFO.:	US 1999-404763		19990924 (9)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 1998-270373	19980925
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	GRANTED	
PRIMARY EXAMINER:	Baxter, Janet	
ASSISTANT EXAMINER:	Ashton, Rosemary	
LEGAL REPRESENTATIVE:	Millen, White, Zelano & Branigan, P.C.	
NUMBER OF CLAIMS:	21	
EXEMPLARY CLAIM:	1	
LINE COUNT:	1654	

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

IT 274248-37-2P

(synthesis of lactone-contg. polymers for resist compns. and method of forming resist pattern using the compn.)

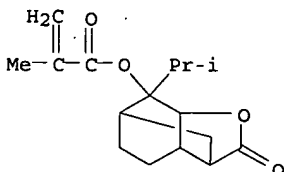
RN 274248-37-2 USPATFULL

CN 2-Propenoic acid, 2-methyl-, octahydro-7-(1-methylethyl)-2-oxo-3,6-methanobenzofuran-7-yl ester, polymer with tetrahydro-2H-pyran-2-yl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 274248-01-0

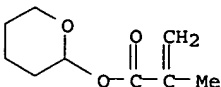
CMF C16 H22 O4



CM 2

CRN 52858-59-0

CMF C9 H14 O3



=> d his

(FILE 'HOME' ENTERED AT 10:15:29 ON 09 SEP 2003)

FILE 'REGISTRY' ENTERED AT 10:15:44 ON 09 SEP 2003

L1 SCREEN 963 AND 970 AND 1006 AND 2067
L2 STRUCTURE UPLOADED
L3 QUE L2 AND L1
L4 15 S L3 SSS SAM

FILE 'CAPLUS, HCAPLUS, USPATFULL' ENTERED AT 10:17:00 ON 09 SEP 2003

L5 69 S L4
L6 9 S L5 AND (FLUORINE OR FLUORINATED OR FLUORO)
L7 8 DUPLICATE REMOVE L6 (1 DUPLICATE REMOVED)

=> d l7 1-8 ibib

L7 ANSWER 1 OF 8 USPATFULL on STN

ACCESSION NUMBER: 2003:106118 USPATFULL
TITLE: Positive-working resist composition
INVENTOR(S): Sato, Kenichiro, Shizuoka, JAPAN
Kodama, Kunihiro, Shizuoka, JAPAN
Aoai, Toshiaki, Shizuoka, JAPAN
PATENT ASSIGNEE(S): FUJI PHOTO FILM CO., LTD. (non-U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 2003073029	A1	20030417
APPLICATION INFO.:	US 2001-22363	A1	20011220 (10)
RELATED APPLN. INFO.:	Division of Ser. No. US 2000-684888, filed on 6 Oct 2000, PENDING		

	NUMBER	DATE
PRIORITY INFORMATION:	JP 1999-285761	19991006
	JP 2000-80519	20000322
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	APPLICATION	
LEGAL REPRESENTATIVE:	SUGHRUE MION, PLLC, 2100 Pennsylvania Avenue, NW, Washington, DC, 20037-3213	
NUMBER OF CLAIMS:	10	
EXEMPLARY CLAIM:	1	
LINE COUNT:	2718	
CAS INDEXING IS AVAILABLE FOR THIS PATENT.		

L7 ANSWER 2 OF 8 USPATFULL on STN

ACCESSION NUMBER: 2003:23576 USPATFULL
TITLE: Positive photosensitive composition
INVENTOR(S): Kodama, Kunihiro, Shizuoka, JAPAN
Sato, Kenichiro, Shizuoka, JAPAN
PATENT ASSIGNEE(S): FUJI PHOTO FILM CO., LTD. (non-U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 2003017415	A1	20030123
APPLICATION INFO.:	US 2002-79414	A1	20020222 (10)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 2001-48602	20010223
	JP 2001-48783	20010223
	JP 2001-48784	20010223
	JP 2001-48880	20010223
	JP 2001-157366	20010525
	JP 2001-157367	20010525
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	APPLICATION	
LEGAL REPRESENTATIVE:	SUGHRUE MION, PLLC, 2100 PENNSYLVANIA AVENUE, N.W., WASHINGTON, DC, 20037	
NUMBER OF CLAIMS:	19	
EXEMPLARY CLAIM:	1	
LINE COUNT:	3838	
CAS INDEXING IS AVAILABLE FOR THIS PATENT.		

L7 ANSWER 3 OF 8 USPATFULL on STN

ACCESSION NUMBER: 2003:17287 USPATFULL
TITLE: Resist composition and patterning process
INVENTOR(S): Kobayashi, Tomohiro, Niigata-ken, JAPAN
Nishi, Tsunehiro, Niigata-ken, JAPAN

Watanabe, Satoshi, Niigata-ken, JAPAN
Kinsho, Takeshi, Niigata-ken, JAPAN
Nagura, Shigehiro, Niigata-ken, JAPAN
Ishihara, Toshinobu, Niigata-ken, JAPAN
Shin-Etsu Chemical Co., Ltd., Tokyo, UNITED STATES,
100-0004 (non-U.S. corporation)

PATENT ASSIGNEE(S):

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 2003013039	A1	20030116
APPLICATION INFO.:	US 2002-170345	A1	20020614 (10)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 2001-181079	20010615
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	APPLICATION	
LEGAL REPRESENTATIVE:	MILLEN, WHITE, ZELANO & BRANIGAN, P.C., 2200 CLARENDON BLVD., SUITE 1400, ARLINGTON, VA, 22201	
NUMBER OF CLAIMS:	3	
EXEMPLARY CLAIM:	1	
LINE COUNT:	1854	
CAS INDEXING IS AVAILABLE FOR THIS PATENT.		

L7 ANSWER 4 OF 8 USPATFULL on STN

ACCESSION NUMBER: 2003:209927 USPATFULL
TITLE: Positive-working resist composition
INVENTOR(S): Sato, Kenichiro, Shizuoka, JAPAN
Kodama, Kunihiro, Shizuoka, JAPAN
Aoai, Toshiaki, Shizuoka, JAPAN
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Kanagawa, JAPAN (non-U.S.
corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 6602646	B1	20030805
APPLICATION INFO.:	US 2000-684888		20001006 (9)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 1999-285761	19991006
	JP 2000-80519	20000322
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	GRANTED	
PRIMARY EXAMINER:	Ashton, Rosemary	
LEGAL REPRESENTATIVE:	Sughrue Mion, PLLC	
NUMBER OF CLAIMS:	5	
EXEMPLARY CLAIM:	1	
NUMBER OF DRAWINGS:	0 Drawing Figure(s); 0 Drawing Page(s)	
LINE COUNT:	2562	
CAS INDEXING IS AVAILABLE FOR THIS PATENT.		

L7 ANSWER 5 OF 8 USPATFULL on STN

ACCESSION NUMBER: 2003:197025 USPATFULL
TITLE: Positive-working photoresist composition
INVENTOR(S): Sato, Kenichiro, Shizuoka, JAPAN
Kodama, Kunihiro, Shizuoka, JAPAN
Aoai, Toshiaki, Shizuoka, JAPAN
Kawabe, Yasumasa, Shizuoka, JAPAN
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Kanagawa, JAPAN (non-U.S.
corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 6596458	B1	20030722
APPLICATION INFO.:	US 2000-563436		20000503 (9)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 1999-127296	19990507
	JP 1999-186607	19990630
	JP 1999-193601	19990707
	JP 1999-193602	19990707
	JP 1999-193603	19990707
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	GRANTED	
PRIMARY EXAMINER:	Chu, John S.	
LEGAL REPRESENTATIVE:	Sughrue Mion, PLLC	
NUMBER OF CLAIMS:	8	
EXEMPLARY CLAIM:	1	

NUMBER OF DRAWINGS: 0 Drawing Figure(s); 0 Drawing Page(s)
LINE COUNT: 1613
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 6 OF 8 USPATFULL on STN

ACCESSION NUMBER: 2002:272716 USPATFULL
TITLE: Polymer, resist composition and patterning process
INVENTOR(S): Nishi, Tsunehiro, Nakakubiki-gun, JAPAN
Nakashima, Mutsuo, Nakakubiki-gun, JAPAN
Tachibana, Seiichiro, Nakakubiki-gun, JAPAN
Funatsu, Kenji, Nakakubiki-gun, JAPAN
PATENT ASSIGNEE(S): Shin-Etsu Chemical Co., Ltd., Tokyo, JAPAN (non-U.S.
corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 2002150835	A1	20021017
APPLICATION INFO.:	US 2002-73223	A1	20020213 (10)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 2001-37247	20010214
	JP 2001-37262	20010214
	JP 2001-37271	20010214
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	APPLICATION	
LEGAL REPRESENTATIVE:	MILLEN, WHITE, ZELANO & BRANIGAN, P.C., 2200 CLARENDON BLVD., SUITE 1400, ARLINGTON, VA, 22201	
NUMBER OF CLAIMS:	4	
EXEMPLARY CLAIM:	1	
LINE COUNT:	1682	

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L7 ANSWER 7 OF 8 CAPLUS COPYRIGHT 2003 ACS on STN DUPLICATE 1

ACCESSION NUMBER: 2001:143826 CAPLUS
DOCUMENT NUMBER: 134:200525
TITLE: Positive-working photoresist composition for far
ultraviolet ray exposure
INVENTOR(S): Aogo, Toshiaki; Sato, Kenichiro; Kodama, Kunihiro
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 55 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001056557	A2	20010227	JP 1999-234240	19990820
PRIORITY APPLN. INFO.:			JP 1999-234240	19990820

L7 ANSWER 8 OF 8 USPATFULL on STN

ACCESSION NUMBER: 2001:212076 USPATFULL
TITLE: Chemically amplified positive resist composition
INVENTOR(S): Uetani, Yasunori, Osaka, Japan
Yamada, Airi, Osaka, Japan
Miya, Yoshiko, Muko-shi, Japan
Takata, Yoshiyuki, Osaka, Japan

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 2001044070	A1	20011122
	US 6579659	B2	20030617
APPLICATION INFO.:	US 2001-824227	A1	20010403 (9)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 2000-101868	20000404
	JP 2000-133328	20000502
	JP 2000-209505	20000711
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	APPLICATION	
LEGAL REPRESENTATIVE:	BIRCH STEWART KOLASCH & BIRCH, PO BOX 747, FALLS CHURCH, VA, 22040-0747	
NUMBER OF CLAIMS:	5	
EXEMPLARY CLAIM:	1	
LINE COUNT:	894	

CAS INDEXING IS AVAILABLE FOR THIS PATENT.